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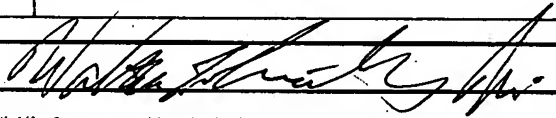
Substitute for form 1449A/PTO				Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Application Number	Not Yet Assigned
				Filing Date	July 11, 2003
				First Named Inventor	Ihl.Hyun.Cho
				Art Unit	Not Yet Assigned
				Examiner Name	Not Yet Assigned
Sheet	1	of	1	Attorney Docket Number	29936/39481

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
W/L		5,668,035	09-16-1997	Fang et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	Foreign Patent Document Country Code ² -Number ³ -Kind Code ⁴ (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶

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OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
WL		Tadahiro Ohmi et al., "Dependence of Thin-Oxide Films Quality on Surface Microroughness," IEEE Transactions on Electron Devices, Vol. 39, No. 3, pp. 537-545 (March 1992)	
WL		C.T. Liu et al., "Severe Thickness Variation of Sub-3nm Gate Oxide Due to Si Surface Faceting, Poly-Si Intrusion, and Corner Stress," 1999 Symposium on VLSI Technology Digest of Technical Papers, pp. 75-76	

Examiner Signature		Date Considered	5/18/04
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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